



3790 USA/DISPLAY/AKT/BG
7828.7017

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:)
KURITA, et al.)
Serial No. 09/464,362)
Filed: December 15, 1999)
For: DUAL SUBSTRATE LOADLOCK)
PROCESS EQUIPMENT)

Group Art Unit: 1763

Examiner: McArthur, S.

#7A
10/20/01
Mw

Assistant Commissioner of Patents
Washington, D.C. 20231

AMENDMENT

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Dear Sirs:

This is in response to the Office Action dated April 11, 2001, which was Paper No. 5 of the present application, response to which is due October 11, 2001 by the enclosed Petition for Extension of Time. Please amend the present application as follows:

IN THE CLAIMS:

Please cancel claims 1-21, 31, 33-37, and 43-97 without prejudice.

Please amend claims 38-42 as follows:

~~11 38. (amended) A substrate processing system comprising:~~
~~at least one processing chamber;~~
~~a transfer chamber connected to said at least one processing chamber; and~~
~~A a loadlock connected to said transfer chamber, said loadlock comprising:~~
~~a single substrate upper support and a single substrate lower support;~~
~~a transfer aperture to transfer a single substrate between said transfer~~
~~chamber and said loadlock;~~
~~an elevator to raise and lower said single substrate upper support and said~~
~~single substrate lower support;~~
~~a cooling plate disposed in said loadlock and positioned to accept a single~~
~~substrate from said single substrate lower support;~~
~~a load/unload aperture through which an unprocessed substrate may be~~